



NAPEX VIRTUAL SYMPOSIUM 2026

FRONTIERS IN NANOSCALE PLASMA ETCHING

OCTOBER 20-21, 2026 | VIRTUAL

Two days of technical presentations, discussion, knowledge exchange and collaboration bringing together the global plasma-processing community.

TECHNICAL FOCUS

- Advanced plasma etching for semiconductor manufacturing
- Emerging materials and atomic layer etching (ALE)
- Cryogenic plasma etching; dielectric and metal etching
- Wide-bandgap semiconductors (GaN, AlGaN)
- MEMS, photonics and quantum applications
- Plasma diagnostics, AI/ML and process characterization
- Sustainability in plasma processing

WHO SHOULD ATTEND

Researchers, students, nanofabrication facility staff, process engineers, semiconductor professionals, equipment manufacturers, national-lab researchers and government scientists.

NAPEX TEAM

Vince Genova
Cornell University (Retired)

Lavendra Mandyam
Stanford University

Ling Xie
Harvard University

Durga Gajula
Georgia Tech

Educate | Collaborate | Innovate | Advance

North American Plasma Etch Exchange (NAPEX)



EVENT DETAILS

Scan for updates & registration



FRONTIERS IN NANOSCALE PLASMA ETCHING

TUESDAY, OCTOBER 20, 2026 | EASTERN TIME (ET)

1:00 PM | NAPEX TEAM | Welcome & Opening Remarks

TIME	AFFILIATION	SPEAKER	TALK TITLE
SESSION 1			
1:10 PM		Marimuthu Rajendiran Si Austrian Labs	PEALE of ultrathin HZO for ferroelectrics
1:40 PM		Ben Jones Oxford Instruments	ALE of AlGaN
SESSION 2			
2:10 PM		Ryan Walsh Univ. of Nevada-Reno	Plasma Assisted Atomic Layer Etching of Al, Nb, and Ta Through Fluorination Based Surface Modification
2:40 PM		Gaurav Thareja AMAT	From Atoms to Systems: Atomic-Layer Engineering for the Next Era of Logic and Memory Technologies
SESSION 3			
3:10 PM		Benoit Hamelin Engenius Micro	Making SiC-on-Insulator Substrates & their etching accessible: challenges, prospects, and commoditization
3:40 PM		Ryan Rivers UC Berkeley	Everyone else's problems show up in etch-an anthology
4:10 PM NAPEX TEAM Closing Remarks			



FRONTIERS IN NANOSCALE PLASMA ETCHING

WEDNESDAY, OCTOBER 21, 2026 | EASTERN TIME (ET)

1:00 PM | NAPEX TEAM | Welcome & Opening Remarks

TIME	AFFILIATION	SPEAKER	TALK TITLE
SESSION 1			
1:10 PM		Paul Plate Sentech	ALE enabling nano-scale semiconductor manufacturing
1:40 PM		Amin Karimi AlixLabs AB	ALE pitch splitting (APS) for patterning high-density silicon structures
SESSION 2			
2:10 PM		Ivy Chen CalTech	Directional ALE of Lithium Niobate for Photonic Integrated Circuits
2:40 PM		Alexis Obu IonQ	Atomic Layer Etching of Diamond by Deliberate Graphitization and Removal
SESSION 3			
3:10 PM		Eknath Sarkar Gtech	Bit Cost Scalable (BiCS) & BEOL-Compatible 4-tier FeRam using high aspect ratio ferroelectric capacitors
3:40 PM		Demis John UCSB	TBD
4:10 PM NAPEX TEAM Closing Remarks			